

| | Hits | Search Text | DBs |
|----|------|--|---|
| 27 | 1 | (immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and (((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or multilayer or bilayer or bi\$4layer or tri\$2layer) same (resist or photoresist or imag\$3)) and (expos\$6 or illuminat\$4 or irradiat\$4) and (CAR or (chemical\$3 near8 amplif\$5 near6 resist) or ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5))) and ((prevent\$5 or avoid\$4) same (infus\$4 or penetrat\$4 or diffus\$3) same protective) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 28 | 5 | (immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and ((multilayer or bilayer or bi\$4layer or tri\$2layer) same (resist or photoresist or imag\$3)) and (expos\$6 or illuminat\$4 or irradiat\$4) and (CAR or (chemical\$3 near8 amplif\$5 near6 resist) or ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5))) and (protective near9 layer) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

| | Hits | Search Text | DBs |
|----|------|---|---|
| 29 | 30 | ((immersion or liquid) near14 (lithograph\$8 or photolitho\$8 or expos\$4)) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and ((multilayer or bilayer or bi\$4layer or tri\$2layer) same (resist or photoresist or imag\$3)) and (expos\$6 or illuminat\$4 or irradiat\$4) and (CAR or (chemical\$3 near8 amplif\$5 near6 resist) or ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5))) and (protective near9 layer) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 30 | 3 | (immersion near22 (lithograph\$8 or photolitho\$8 or expos\$4)) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and (((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or multilayer or bilayer or bi\$4layer or tri\$2layer) same (resist or photoresist or imag\$3)) and ((prevent\$5 or avoid\$4) same (infus\$4 or penetrat\$4 or diffus\$3) same protective) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 31 | 6 | (immersion near22 (lithograph\$8 or photolitho\$8 or expos\$4)) and ((prevent\$5 or avoid\$4) same (infus\$4 or penetrat\$4 or diffus\$3) same (protective near12 layer) same (photoresist or resist or photosensitive or imag\$3 or photoimag\$5)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

| | Hits | Search Text | DBs |
|----|------|--|---|
| 32 | 10 | ((immersion near22 (lithograph\$8 or photolitho\$8 or expos\$4)) or IML) and ((prevent\$5 or avoid\$4) same (infus\$4 or penetrat\$4 or diffus\$3 or interact\$5) same ((protective near12 layer) or topcoat) same (photoresist or resist or photosensitive or imag\$3 or photoimag\$5)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 33 | 5 | ((immersion near22 (lithograph\$8 or photolitho\$8 or expos\$4)) or IML) and (((protective near12 layer) or topcoat) same (photoresist or resist or photosensitive or imag\$3 or photoimag\$5) same ((chemical\$5 near9 amplif\$4 near5 resist) or PAG or (photoacid near5 generat\$4) or (acid near6 (diffus\$4 or generat\$4)))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 34 | 23 | ((((protective near12 layer) or topcoat) same (photoresist or resist or photosensitive or imag\$3 or photoimag\$5) same ((chemical\$5 near9 amplif\$4 near5 resist) or PAG or (photoacid near5 generat\$4) or (acid near6 (diffus\$4 or generat\$4)))) same (diffusion or penetrat\$\$ or infus\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |